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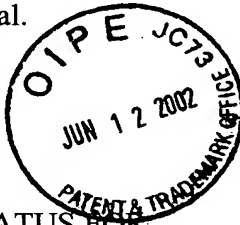
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Gopinath et al.

Application No.: 10/016,017

Filed: December 12, 2001

Title: METHOD AND APPARATUS FOR
INTRODUCTION OF SOLID PRECURSORS
AND REACTANTS INTO A SUPERCRITICAL
FLUID REACTOR



Attorney Docket No.:
NOVLP030/NVLS-000497

Examiner: Not yet assigned

Group: 2812

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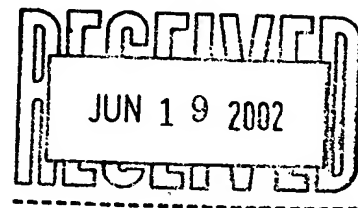
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Tara Hayden

INFORMATION DISCLOSURE STATEMENT
37 CFR §§1.56 AND 1.97(b)

Commissioner for Patents
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Dear Sir:

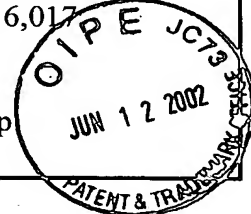


The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

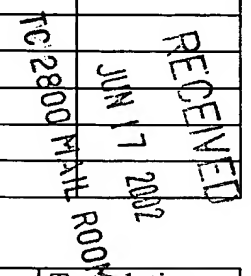
This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NOVLP030/NVLS-000497	Application No.: 10/016,017
	Applicant: Gopinath et al. Filing Date December 12, 2001	Group 2812



U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date



Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	A	Biberger et al., "High Pressure Processing Chamber for Semiconductor Substrate", Pub. No. US 2002/0046707 A1, Pub. Date: April 25, 2002, Appl. No.: 09/912,844, Filed: July 24, 2001, pp. 1-19.
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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